

Horizontal Sputtering Systems



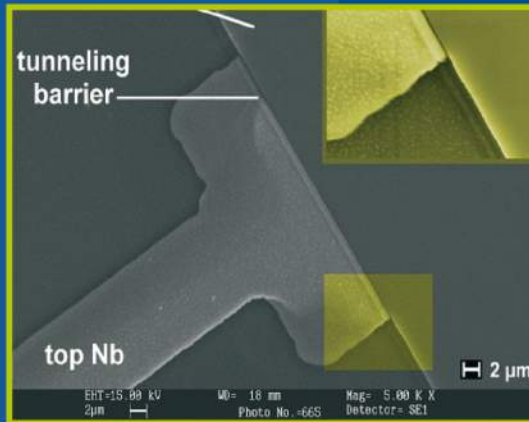
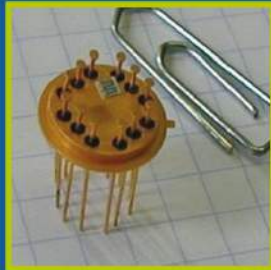
“Horizontal sputtering model KS 500 H”

Kenosistec horizontal sputtering systems are designed and realized to provide excellent UNIFORMITY, flexibility and easy handling of substrates. These features make them the ideal tools for R&D ACTIVITIES and process development. A full range of options is available to optimize their performances for special applications.

The KS 500 H “dual chamber” eliminates any source of cross contamination, allowing the realization of the most sophisticated processes. Chambers can be used either simultaneously or separately, in order to deposit complex multilayer structures. The sequence of the deposition can be varied over a wide range of parameters with a highly effective separation of DC and RF sources.



“Horizontal sputtering model KS 500 H Dual Chamber”



APPLICATIONS

Thin film structures of metals, semiconductor and oxides for **Aerospace, Microelectronics, Sensors, Automotive, Optics, Telecom, Energy.**



GENERAL FEATURES

Configuration

Sputter up or sputter down

Substrate handling

All the KS Horizontal models include automatic handling of the substrate holder. Optional devices for substrate heating or cooling are available. Planetary rotation of the pallet can be added as well as an optional Load Lock chamber.

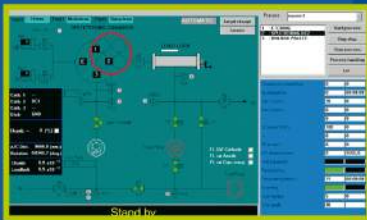


Co-sputtering

Sequential or Confocal capability Circular cathodes from 1" to 10"

Gas & Pressure

Up to 5 independent MFCs with individual shut off valve Upstream and Downstream pressure control.



Process controller

PC-PLC system. Fully automatic and manual operation with safety interlocks. Advanced editing functions. Remote assistance.

TECHNICAL SPECIFICATIONS

Chamber dimensions, mm
Magnetron Cathodes
DC Power Supplies
RF Power Supplies
Substrate Heating
Substrate Cooling
Substrate Etching/Bias
Ultimate Pressure
Pumping System

KS 500 H

Ø 500, h 300
4 x up to 6"
Up to 2500W
Up to 1500 W

KS 500 H DUAL CHAMBER

2 x Ø 500, h 300
4 x up to 6"
Up to 2500W
Up to 1500 W
Up to 350 °C - option up to 800°C
Water or LN circulation
RF/DC up to 600W
5 x 10⁻⁷ mbar (10⁻⁹ range for UHV models)
Cryo or turbomolecular

KS 800 H

Ø 800, h 300
4 x up to 10"
Up to 5000W
Up to 3000 W

Kenosistec srl is a company of Angelantoni Group www.angelantoni.it

Kenosistec s.r.l. Headquarters and Plant

Viale delle Scienze, 23 20082 Binasco Milano Tel. +39 02.9055200 Fax +39 02.9052984 info@kenosistec.it www.kenosistec.it